


INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i> <div style="border: 1px solid black; border-radius: 50%; width: 100px; height: 100px; display: flex; align-items: center; justify-content: center; margin: 0 auto;"> <div style="writing-mode: vertical-rl; transform: rotate(180deg); font-size: 8px;">PATENT & TRADEMARK OFFICE</div> <div style="text-align: center;"> OCT 20 2004 <small>CAS 3</small> </div> </div>				Docket Number (Optional) FIS920040210US1		Application Number 10/711,369		
				Applicant(s) Venigalla, et al.				
				Filing Date September 14, 2004		Group Art Unit 3723		
U.S. PATENT DOCUMENTS								
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
U.S. PATENT APPLICATION PUBLICATIONS								
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
G.A.		20040040217	03/04/2004	Takashina, et al.	—	—		
		20030211747	11/13/2003	Hedge, et al.	—	—		
		20030092271	05/15/2003	Jindal, et al.	—	—		
		20030047710	03/13/2003	Babu, et al.	—	—		
FOREIGN PATENT DOCUMENTS								
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
OTHER DOCUMENTS <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>								
G.A.		Prior Art - CHEMICAL PROCESSES IN GLASS POLISHING, Cook L.M., J. of Non-crystalline Solids, Vol. 120, pp 152-171.						
G.A.		A CMP MODEL COMBINING DENSITY AND TIME DEPENDENCIES, Taber H. Smith, et al., 1999 CMP-MIC conference proceedings.						
EXAMINER Jacob K. Achon Jr.				DATE CONSIDERED 7/13/05				
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								

 <p>INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)</p>	Docket Number (Optional) FIS92004-0210US1	Application Number 10/711,369
	Applicant(s) Venigalla, et al.	
	Filing Date September 9, 2004	Group Art Unit 3723

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

U.S. PATENT APPLICATION PUBLICATIONS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO

OTHER DOCUMENTS *(Including Author, Title, Date, Pertinent Pages, Etc.)*

J.M.		CHEMICAL MECHANICAL PLANARIZATION OF MICROELECTRONIC MATERIALS , John Wiley and Sons, Inc., Wiley-Interscience publication, by Joseph M. Steigerwald, Shyam P. Murarka, Ronald J. Gutmann, year 1997, pages 140-147

EXAMINER Jacob K. Ackon Jr.	DATE CONSIDERED 7/13/05
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